



-	4	((topography or "step height") same ((width or line) with variation) same ("isolation region" or STI or "trench isolation"))	USPAT; US-PGPUB	2003/05/22 18:16
-	10	((topography or "step height") same ((width or line) with variation) )and ("isolation region" or STI or "trench isolation"))	USPAT; US-PGPUB	2003/05/22 17:05
-	1380	((438/FOR.142).ccls.)	EPO; JPO; DERWENT	2003/05/22 17:08
-	0	((438/FOR.142).ccls.) and sti	EPO; JPO; DERWENT	2003/05/22 17:09
-	4	((438/FOR.142).ccls.) and trench	EPO; JPO; DERWENT	2003/05/22 17:09
-	0	((438/FOR.142).ccls.) and "step height"	EPO; JPO; DERWENT	2003/05/22 17:10
-	1	((438/FOR.142).ccls.) and ((line or width) with variation)	EPO; JPO; DERWENT	2003/05/22 17:10
-	3	((438/FOR.142).ccls.) and (CD or "critical dimension" or "lateral dimension")	EPO; JPO; DERWENT	2003/05/22 18:14
-	465	(topography or "step height") same ("isolation region" or STI or "trench isolation"))	USPAT; US-PGPUB	2003/05/22 18:17
-	436	((topography or "step height") same ("isolation region" or STI or "trench isolation")) and (gate or electrode or polysilicon or poly or line)	USPAT; US-PGPUB	2003/05/22 18:18
-	2	((topography or "step height") same ("isolation region" or STI or "trench isolation")) and (gate or electrode or polysilicon or poly or line) and (metrology or scatterom\$5)	USPAT; US-PGPUB	2003/05/22 18:19
-	1331	(CMP or polish\$3 or "chemical mechanical") same (((lateral or width or critical) near3 (dimension or uniformity or error or bias or tolerance or variation)) or CD)	USPAT; US-PGPUB	2003/05/22 18:25
-	889	(CMP or polish\$3 or "chemical mechanical") same (((lateral or width or critical) near3 (dimension or uniformity or error or bias or tolerance or variation)) )	USPAT; US-PGPUB	2003/05/22 18:26
-	174	(438/32).CCLS.	USPAT; US-PGPUB	2003/05/22 18:31
-	33	(CMP or polish\$3 or "chemical mechanical") and (profile same (compar\$3 or measur\$3 or match\$3)) and ((CD or "critical dimension") with (variation or variance)) and planariz\$6	USPAT; US-PGPUB	2003/05/23 07:15
-	1368	(polish\$3) with (STI or trench) with oxide	USPAT; US-PGPUB	2003/05/23 07:15
-	68	((polish\$3) with (STI or trench) with oxide) and ((width or line) with (variation or variance))	USPAT; US-PGPUB	2003/05/23 07:41
-	576	((control\$4) with (polish\$3 or planariz\$5)) same (parameter or recipe)	USPAT; US-PGPUB	2003/05/23 08:06
-	68	((control\$4) with (polish\$3 or planariz\$5)) same (parameter or recipe) and (STI or "trench isolation" or "isolation region")	USPAT; US-PGPUB	2003/05/23 08:07
-	75	((control\$4) with (polish\$3 or planariz\$5)) same (parameter or recipe) and ((lateral or width or critical) near3 (dimension or uniformity or error or bias or tolerance or variation))	USPAT; US-PGPUB	2003/05/23 08:23
-	17	((control\$4) with (polish\$3 or planariz\$5)) same (parameter or recipe) and ((lateral or width or critical) near3 (dimension or uniformity or error or bias or tolerance or variation)) ) and grating	USPAT; US-PGPUB	2003/05/23 08:17

-	1	("6,054,868").PN.	USPAT; US-PGPUB	2003/05/23 08:17
-	58	(((control\$4) with (polish\$3 or planariz\$5)) same (parameter or recipe)) and ((lateral or width or critical) near3 (dimension or uniformity or error or bias or tolerance or variation)) ) not (((control\$4) with (polish\$3 or planariz\$5)) same (parameter or recipe)) and ((lateral or width or critical) near3 (dimension or uniformity or error or bias or tolerance or variation)) ) and grating)	USPAT; US-PGPUB	2003/05/23 08:27
-	5568	(reduc\$3 or control\$5) with (CD or critical or lateral or width) with (variation or variance)	USPAT; US-PGPUB	2003/05/23 09:54
-	23	((reduc\$3 or control\$5) with (CD or critical or lateral or width) with (variation or variance)) same (CMP or polish\$3)	USPAT; US-PGPUB	2003/05/23 08:32
-	1	("6458015").PN.	USPAT; US-PGPUB	2003/05/23 08:32
-	5	("5420796"   "5917332"   "5971586"   "5972727"   "6016562").PN.	USPAT	2003/05/23 08:46
-	1372	((reduc\$3 or control\$5) with (CD or critical or lateral or width) with (variation or variance)) and feedback	USPAT; US-PGPUB	2003/05/23 09:54
-	98	((reduc\$3 or control\$5) with (CD or critical or lateral or width) with (variation or variance)) and feedback) and (cmp or polish\$3)	USPAT; US-PGPUB	2003/05/23 10:22